

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1-44. Canceled

45. (Currently Amended) An optical arrangement, comprising:

a light source that emits radiation during operation of the optical arrangement;[[,]]

a mount[[,]];

an optical element ~~fastened in said mount, ; and~~

a connecting structure that fastens the optical element to the mount, the connecting structure being configured so that a thermal conductivity of the connecting structure has a symmetry characteristic that substantially does not correspond to the shape of the optical element,

wherein, during operation of the optical arrangement, said the optical element is acted on by said the radiation such that a heat supply results from said the radiation that lacks symmetry corresponding to the shape of said the optical element, and a connecting structure between said mount and said optical element, having a symmetry characteristic that substantially does not correspond to the shape of the optical element,

the optical arrangement is an optical arrangement of a microlithography projection exposure system.

46. (Currently Amended) An optical arrangement, comprising:

a light source that emits radiation during operation of the optical arrangement;[[,]]

a mount;[[,]]

an optical element ~~fastened in said mount;~~ and

a single- or multi-part thermally conducting element which fastens the optical element to the mount,

wherein, during operation of the optical arrangement, said the optical element is acted on by ~~said the~~ the radiation such that heat that results from ~~said the~~ the radiation lacks symmetry corresponding to the shape of ~~said the~~ the optical element, ~~and a single- or multi-part thermally conducting element arranged in operative connection with said optical element and said mount and having a form the~~ single- or multi-part thermally conducting element is configured to provide heat transport that effects an at least partial compensation of the asymmetry of temperature distribution in said the optical element, and

the optical arrangement is an optical arrangement of a microlithography projection exposure system.

47-48. Canceled

49. (Currently Amended) The optical arrangement according to claim 80, in which ~~said~~ the optical element comprises a transmitting element.

50. (Currently Amended) The optical arrangement according to claim 49, in which ~~said~~ the transmitting element comprises a lens.

51-54. Canceled

55. (Currently Amended) The ~~projection-exposure~~ system according to claim 84, in which ~~said~~ the optical element comprises a transmitting element.

56. (Currently Amended) The ~~projection-exposure~~ system according to claim 55, in which ~~said~~ the transmitting element comprises a lens.

57. (Currently Amended) The optical arrangement according to claim 80, in which ~~said~~ the optical element comprises a mirror.

58-59. Canceled

60. (Currently Amended) The ~~projection-exposure~~ system according to claim 84, in which ~~said~~ the optical element comprises a mirror.

61. (Original) The optical arrangement according to claim 80, having a slit-shaped image field.

62-63. Canceled

64. (Currently Amended) The ~~projection-exposure~~ system according to claim 84, having a slit- shaped image field.

65. (Withdrawn – Currently Amended) The optical arrangement according to claim 80, in which ~~said~~ the optical element is arranged near a field plane.

66. (Withdrawn – Currently Amended) The optical arrangement according to claim 65, in which ~~said~~ the optical element is arranged near a field plane.

67. Canceled

68. (Withdrawn – Currently Amended) The ~~projection-exposure~~ system according to claim 84, in which ~~said~~ the optical element is arranged near a field plane.

69. (Withdrawn) The optical arrangement according to claim 80, further comprising a reticle, the illumination of which lacks rotational symmetry.

70. (Withdrawn) The optical arrangement according to claim 69, in which ~~said~~ the reticle illumination consists of off- axis, dipole or quadrupole illumination.

71-75. Canceled

76. (Withdrawn - Currently Amended) The ~~projection-exposure~~ system according to claim 84, further comprising a reticle, the illumination of which lacks rotational symmetry.

77. (Withdrawn - Currently Amended) The ~~projection-exposure~~ system according to claim 76, in which ~~said~~ the reticle illumination consists of off-axis, dipole or quadrupole illumination type.

78. (Withdrawn - Currently Amended) The ~~projection-exposure~~ system according to claim 84, in which said optical element is arranged near a pupil plane.

79. Canceled

80. (Currently Amended) An optical arrangement comprising:

a light source that emits radiation during operation of the optical arrangement;[[,]]

a mount;[[,]]

an optical element fastened to ~~said~~ the mount; and[[,]]

a single- or multi-part passive thermally conducting element arranged in operative connection with the optical element, the single- or multi-part thermally conducting element comprising an assembly of portions of different materials, the different materials having different thermal conductivities,

wherein, during operation of the optical arrangement, ~~said the~~ optical element is acted on by ~~said the~~ radiation such that heat that results from ~~said the~~ radiation lacks symmetry corresponding to the shape of ~~said the~~ optical element, ~~and a single- or multi-part passive thermally conducting element arranged in operative connection with said optical element and said mount and having a form of the assembly of portions of different materials are configured to conduct heat away from the optical element to effect heat transport that effects an at least partial compensation of the asymmetry of temperature distribution in said the optical element, wherein said passive thermally conducting element comprises an assembly of portions of different material and the optical arrangement is an optical arrangement of a microlithography projection exposure system.~~

81. (Currently Amended) The optical arrangement according to claim 80, in which ~~said~~ the connecting structure comprises adjustable portions.

82. (Currently Amended) The optical arrangement according to claim 84, in which ~~said~~ the thermally conducting element is adjustable.

83. (Currently Amended) The ~~projection exposure~~ system according to claim 84, in which ~~said the~~ thermally conducting elements comprise adjustable portions.

84. (Currently Amended) A ~~projection exposure~~ system comprising:

a light source that emits radiation during operation of the system;

an optical element that, during operation of the system, is heated by the radiation in a manner that lacks rotational symmetry;[[,]] and

a cooling system for ~~said~~ the optical element ~~that lacks rotational symmetry~~, said the cooling system lacking rotational symmetry and comprising including passive thermally conducting devices that effect cooling of the optical element,

wherein ~~said~~ the passive thermally conducting devices comprise portions of different material having different thermal conductivities and arranged to conduct heat asymmetrically from the optical element ,and
the system is a microlithography projection exposure system.

85-89. Canceled

90. (Currently Amended) An optical arrangement according to claim 80, wherein ~~said~~ the optical element is selected from a group consisting of mirrors, lenses, prisms and transmitting elements.

91. (New) The optical arrangement according to claim 45, wherein the connecting structure comprises a plurality of webs.

92. (New) The optical arrangement according to claim 91, wherein one or more of the plurality of webs comprise a first material and one or more of the plurality of webs comprises a second material different from the first material.

93. (New) The optical arrangement according to claim 92, wherein the first material has a higher thermal conductivity than the second material.
94. (New) The optical arrangement according to claim 93, wherein the radiation incident on the optical element has a slit-shaped cross-section.
95. (New) The optical arrangement according to claim 94, wherein the one or more webs comprising the first material are positioned closer than the webs comprising the second material to a long axis of the slit-shaped cross section of the radiation incident on the optical element. .
96. (New) The optical arrangement according to claim 92, wherein the first material is silver and the second material is aluminum or lead.
97. (New) The optical arrangement according to claim 45, wherein the optical element is a lens.
98. (New) The optical arrangement according to claim 45, wherein the connecting structure passively reduces asymmetrical heating of the optical element due to the radiation during operation of the optical arrangement.
99. (New) The optical arrangement according to claim 46, wherein the connecting structure comprises a plurality of webs.
100. (New) The optical arrangement according to claim 99, wherein one or more of the plurality of webs comprise a first material and one or more of the plurality of webs comprises a second material different from the first material.

101. (New) The optical arrangement according to claim 100, wherein the first material has a higher thermal conductivity than the second material.
102. (New) The optical arrangement according to claim 101, wherein the radiation incident on the optical element has a slit-shaped cross-section.
103. (New) The optical arrangement according to claim 102, wherein the one or more webs comprising the first material are positioned closer than the webs comprising the second material to a long axis of the slit-shaped cross section of the radiation incident on the optical element.
104. (New) The optical arrangement according to claim 100, wherein the first material is silver and the second material is aluminum or lead.
105. (New) The optical arrangement according to claim 46, wherein the optical element is a lens.
106. (New) The optical arrangement according to claim 46, wherein the connecting structure passively reduces asymmetrical heating of the optical element due to the radiation.
107. (New) The optical arrangement according to claim 46, wherein the single- or multi-part thermally conducting element wherein the connecting structure passively reduces asymmetrical heating of the optical element due to the radiation during operation of the optical arrangement.